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(21) International Application Number: PCT/US95/16786 (22) International Filing Date: 21 December 1995 (21.12.95) (30) Priority Data: 08/366,634 30 December 1994 (30.12.94) US (71) Applicant: HOECHST CELANESE CORPORATION [US/US]; Route 202-206 North, Somerville, NJ 08876 (US). (72) Inventors: RAHMAN, M., Dalil; 62 Concord Ridge Road, Flemington, NJ 08822 (US). AUBIN, Daniel, P.; 202 Congdon Road, Voluntown, CT 06384 (US). (74) Agents: SAYKO, Andrew, F., Jr. et al.; Hoechst Celanese Corporation, 70 Meister Avenue, Somerville, NJ 08876 (US).		(81) Designated States: CN, JP, KR, <u>SG</u> , European patent (AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: ISOLATION OF NOVOLAK RESIN BY LOW TEMPERATURE SUB-SURFACE FORCED STEAM DISTILLATION (57) Abstract A water insoluble, aqueous alkali soluble novolak resin, process for producing such a novolak resin, a photoresist containing such a novolak resin, and a method for producing a semiconductor device, wherein the resin is isolated by sub-surface forced steam distillation.		